

## Corrigendum

### Correction to “P-94: Strategies for Adjusting the Flowability of Photoresist from Aspects of Material Composition and Manufacturing Process”

Feng, Y., Li, J. and Zhang, M. (2024), P-94: Strategies for Adjusting the Flowability of Photoresist from Aspects of Material Composition and Manufacturing Process. SID Symposium Digest of Technical Papers, 55: 1751-1754. <https://doi.org/10.1002/sdtp.17911>

The affiliations of the authors were listed incorrectly and in the wrong order in the published version:

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We apologize for this error.